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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/652,550
Filing Date August 31, 2000
Inventor Keiji Jono et al.
Assignee KMT Semiconductor, LTD
Group Art Unit 2811
Examiner Quang D. Vu
Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor, Trench Isolation Structures Formed in a Semiconductor, Memory Cells and DRAMS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References—See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 3-10-03

By: 

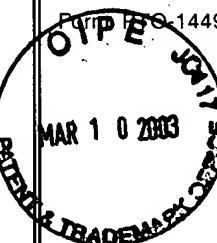
D. Brent Kenady
Reg. No. 40,045

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 <p style="text-align: center;">LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. KM1-001	SERIAL NO. 09/652,550	
		APPLICANT: Keiji Jono et al.				
		FILING DATE August 31, 2000		GROUP 2811		
		U.S. PATENT DOCUMENTS				
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA 6,034,409	03/07/2000	Sakai et al.			
	AB 6,171,924 B1	01/09/2001	Wang et al.			
	AC 6,154,417	11/28/2000	Kim			
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
FOREIGN PATENT DOCUMENTS						
	Document Number	Date	Country	Class	Subclass	Translation
						Yes
	AL					
	AM					
	AN					
	AO					
	AP					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)						
	AR					
	AS					
	AT					
EXAMINER			DATE CONSIDERED			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>						

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